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AM-5630.P1

INFORMATION DISCLOSURE  
STATEMENT BY APPLICANT

(Use several sheets if necessary)

Chentsau Ying et al.  
Applicants

November 16, 2001  
Filing Date

Unknown  
Group



U. S. PATENT DOCUMENTS

Examiner Initial	Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
<u>LV</u>	5,811,356	09/22/98	Muruges et al.	438	711	
	5,824,375	10/20/98	Gupta	427	569	
	6,020,035	02/01/00	Gupta et al.	427	534	
	6,103,055	08/15/00	Maher et al.	156	345	
	6,121,161	09/19/00	Rossmann et al.	438	783	
<u>LV</u>	6,143,078	11/07/00	Ishikawa et al.	118	715	

FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Publication Date	Name	Class	Subclass	Translation If Appropriate
<u>LV</u>	EP 0892083	01/20/99	Qiao et al.	C23C	16/44	

Examiner Date Considered

LAN VINH

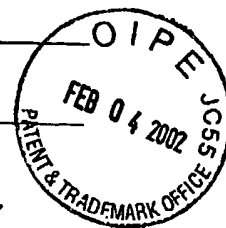
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\* Provided by the Applicant.

\*\* Cited in the specification by Applicant.

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)



- LV J. Hughes et al., "Dry Etch Sequencing Induced Gate Oxide Degradation due to Metallic Contamination in 0.25  $\mu\text{m}$  CMOS Manufacturing", *International Electronic Devices Meeting*, pp.337-340 (1998).
- LV K. K. Singh et al., "Residual  $\text{CF}_x$  Radicals From Periodic Dry Cleans of  $\text{Ar}^+$  Sputter Etch Chamber: Causes and Process Consequences", *Electrochemical Society Proceedings*, Vol. 31, pp.182-189 (1997).
- LV S. Tehrani et al., "Progress and Outlook for MRAM Technology", *IEEE Transactions on Magnetics*, Vol. 35, No. 5, pp.2814-2819. (Sept 1999).

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11/18/04

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